09695715 CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returne d

From A Search of 09695715 on October 25, 2001

| 3 | | | OR, 3 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
|-----|-------------------------------------|-----------|---|
| | 438/689 438/690 | | CHEMICAL ETCHING .Combined with the removal of material by nonchemical means (e.g., ablating, abradi |
| ng, | etc.) 438/691 | | Combined mechanical and chemical material |
| | 438/692 | | <pre>removalSimultaneous (e.g., chemical-mechanical polishing, etc.)</pre> |
| 2 | , | 330 | OR, 2 XR) : AMPLIFIERS WITH SEMICONDUCTOR AMPLIFYING DEVICE (E.G., TRANSISTOR) .Including gain control means |
| | 330/285 | | Having particular biasing means |
| 2 | 340/825 | 340 36 | OR, 2 XR) : COMMUNICATIONS: ELECTRICAL SELECTIVE .Having indication or alarm (e.g., location indication)Code responsive (i.e., paging) |
| | 340/7.58 | | Alert |
| 2 | Class | 342 | OR, 2 XR) : COMMUNICATIONS: DIRECTIVE RADIO WAVE SYSTEMS AND DEVICES DETERMINING DISTANCE .With frequency modulation |
| 2 | | 342 | OR, 1 XR) : COMMUNICATIONS: DIRECTIVE RADIO WAVE SYSTEMS AND DEVICES WITH PARTICULAR CIRCUIT |
| 2 | 342/70 Class 342/61 342/70 | | OR, 1 XR) : COMMUNICATIONS: DIRECTIVE RADIO WAVE SYSTEMS AND DEVICES RETURN SIGNAL CONTROLS EXTERNAL DEVICE .Radar mounted on and controls land vehicle |
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|) | 2 | 348/554 Class 348/553 348/554 | 348 | : TELEVISION BASIC RECEIVER WITH ADDITIONAL FUNCTION |
|---|---|--|-----|---|
| | 2 | 375/261 Class 375/259 | 375 | OR, 1 XR) : PULSE OR DIGITAL COMMUNICATIONS SYSTEMS USING ALTERNATING OR PULSATING CURRENT |
| | | 375/260 375/261 | | .Plural channels for transmission of a single pulse trainQuadrature amplitude modulation |
| | 2 | 438/424 Class | | OR, 0 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | | 438/400 438/424 | | FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE STRUCTURE Grooved and refilled with deposited dielectri |
| С | | | | material |
| | 2 | 438/427 Class | | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | | 438/400 438/424 | | FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE STRUCTURE .Grooved and refilled with deposited dielectri |
| С | | 438/427 | | <pre>materialRefilling multiple grooves of different widths or depths</pre> |
| | 2 | 438/435 Class | | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | | 438/400 | | FORMATION OF ELECTRICALLY ISOLATED LATERAL |
| С | | 438/424 | | SEMICONDUCTIVE STRUCTURE .Grooved and refilled with deposited dielectri |
| | | 438/435 | | <pre>materialMultiple insulative layers in groove</pre> |
| | | | | |

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| | 438/400 | FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE STRUCTURE |
| | 438/439 | <pre>.Recessed oxide by localized oxidation (i.e., LOCOS)</pre> |
| | 438/443 | Etchback of recessed oxide |
| 2 | 438/700 Class | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | 438/689 438/694 438/700 | CHEMICAL ETCHING .Combined with coating stepFormation of groove or trench |
| 2 | 438/701 Class | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | 438/689 438/694 438/700 438/701 | CHEMICAL ETCHING .Combined with coating stepFormation of groove or trenchTapered configuration |
| 2 | 438/702 Class | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | 438/689 438/694 438/700 438/702 | CHEMICAL ETCHING .Combined with coating stepFormation of groove or trenchPlural coating steps |
| 2 | 438/792 Class | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | 438/758 | COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR REGION OR OF SEMICONDUCTOR SUBSTRATE |
| | 438/778 | .Insulative material deposited upon semiconductive substrate |
| | 438/791 438/792 | Silicon nitride formationUtilizing electromagnetic or wave energy |
| c.) | | (e.g., photo-induced deposition, plasma, et |
| 2 | 438/793 Class | OR, 2 XR) : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS |
| | 438/758 | COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR |
| | 438/778 | REGION OR OF SEMICONDUCTOR SUBSTRATE .Insulative material deposited upon |

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| tc.) | 438/791 438/792 | 09695715_CLSTITLES semiconductive substrateSilicon nitride formationUtilizing electromagnetic or wave energy (e.g., photo-induced deposition, plasma, e | | | |
|------|--------------------|---|--|--|--|
| ((,) | 438/793 | Organic reactant | | | |
| 2 | 438/794 | (0 OR, 2 XR) | | | |
| | Class | 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS | | | |
| | 438/758 | COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR REGION OR OF SEMICONDUCTOR SUBSTRATE | | | |
| | 438/778 | .Insulative material deposited upon semiconductive substrate | | | |
| | 438/791 | Silicon nitride formation | | | |
| | 438/794 | Organic reactant | | | |

09695715 CLS

Most Frequently Occurring Classifications of Patents Returned From A Search of 09695715 on October 25, 2001

Original Classifications

- 2 348/554
- 2 438/424

Cross-Reference Classifications

- 3 438/692
- 2 330/285
- 2 340/7.58
- 2 342/128
- 2 438/427
- 2 438/435
- 2 438/443
- 2 438/700
- 2 438/701
- 2 438/702
- 2 438/792
- 2 438/793
- 2 438/794

Combined Classifications

- 3 438/692
- 2 330/285
- 2 340/7.58
- 2 342/128
- 2 342/175
- 2 342/70
- 2 348/554
- 2 375/261
- 2 438/424
- 2 438/427
- 2 438/435
- 2 438/443
- 2 438/700
- 2 438/701
- 2 438/702
- 2 438/792
- 2 430/132
- 2 438/7932 438/794

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PLUS Search Results for S/N 09695715, Searched October 25, 2001

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